

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. 10/293,164
Priority Filing Date November 12, 2002
 Inventor J. Brett Rolfson
 Assignee Micron Technology, Inc.
Priority Group Art Unit 1765
Priority Examiner Kathleen Duda
 Attorney Docket No. MI22-2482
 Customer No. 021567
 Title: Ion Implant Lithography Method of Processing a Semiconductor Substrate

INFORMATION DISCLOSURE STATEMENT
PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98


In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation application of co-pending application Serial No. 10/293,164, filed November 12, 2002. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. § 1.98(d) and MPEP § 609(2).

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 1-12-04

By: 
 Mark S. Matkin
 Reg. No. 32,268

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| Form PTO-1449 | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | ATTY. DOCKET NO. MI22-2482 | | PRIORITY SERIAL NO. 10/293,164 | |
| LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) | | | | APPLICANT: J. Brett Rolfson | | | |
| | | | | PRIORITY FILING DATE November 12, 2002 | | PRIORITY GROUP ART NO. 1756 | |

| U.S. PATENT DOCUMENTS | | | | | | | |
|-------------------------|-----------------|----------|---------------|-------|----------|-------------------------------|--|
| *Examiner's Initials | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate | |
| AA | 4,377,437 | 03/22/83 | Taylor et al. | | | | |
| AB | 5,853,925 | 12/29/98 | Huh | | | | |
| AC | 6,042,996 | 03/28/00 | Lin et al. | | | | |
| AD | 6,232,229 B1 | 05/15/01 | Reinberg | | | | |
| AE | | | | | | | |
| AF | | | | | | | |
| AG | | | | | | | |
| AH | | | | | | | |
| AI | | | | | | | |

| FOREIGN PATENT DOCUMENTS | | | | | | | | |
|--------------------------|-----------|----------|------------------------|----------|-------------|----|--|--|
| Document Number | Date | Country | Class | Subclass | Translation | | | |
| | | | | | Yes | No | | |
| AJ | 59-53842 | 03/28/84 | Japan (Seichi et al.) | | | | | |
| AK | 61-177720 | 08/09/86 | Japan (Hiroaki et al.) | | | | | |
| AL | | | | | | | | |

| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | |
|---|--|---|
| AM | | Adesida et al., <i>The range of light ions by polymeric resists</i> , J. APPL. PHYS. 56 (6), pp. 1801-1807 (September 15, 1984). |
| AN | | Melngailis et al., <i>A review of ion projection lithography</i> , J. Vac. Sci. Technol. B 16(3), pp. 927-956 (May/June 1998). |
| AO | | |
| EXAMINER | | DATE CONSIDERED |

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.